



High Voltage Trench Schottky Diode

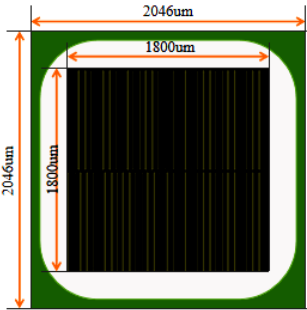
FEATURES

- Trench MOS Schottky technology
- Die in 6" Wafer Form
- 100V, 10A*
- $V_F=0.63V(\text{typ.})^{**}$

Electrical Characteristics (T_j=25°C)

| Parameter | Description | Min. | Typ. | Max. | Unit | Test Condition |
|---|---|--------------------|------|------|------|------------------------|
| V _{RRM} | Maximum repetitive peak reverse voltage | 105 | 113 | — | V | I _R = 500μA |
| V _F | Static Forward Voltage | — | 0.38 | 0.49 | V | I _F = 1A |
| | | — | 0.51 | 0.55 | V | I _F = 5A |
| | | — | 0.63 | 0.75 | V | I _F = 10A |
| I _R *** | Cathode-to-anode Leakage Current | — | 18 | 50 | μA | V _R = 100V |
| T _J , T _{STG} | Operating and Storage Temperature Range | -55°C to 150°C Max | | | | |
| *** Pulse width < 300 uS, Duty cycle < 2% | | | | | | |

Mechanical Data

| | | | |
|---------------------------------|---|-----------------|---|
| Die Size | 2106×2106 | μm ² | CHIP DRAWING (Scribe Line is Excluded)  |
| Source Pad Size | 1800 × 1800 | μm ² | |
| Scribe Line Size | 60 | μm | |
| Wafer Diameter | 6 | in | |
| Wafer Thickness | 250 | μm | |
| Estimated Gross Die | 3611 (Yield > 98%) | | |
| Anode Metal Thickness | Al\Ti\Ni\Ag(2.8um\0.1um\0.2um\1.8um) | | |
| Cathode Metal Thickness | Ti\Ni\Ag(0.2um\0.3um\2um) | | |
| Recommended Storage Environment | Store in original container, in dry nitrogen, < 6 months at an ambient temperature of 23°C±3°C > | | |

* Electrical characteristics are reported for the reference packaged part (TO-220) and can not be guaranteed in die sales form.

** Electrical characteristics are reported for the bare die. Variations in customer packaging materials, dimensions and processes may affect parametric performance.